

**REMARKS****Interview**

Applicant wishes to express its appreciation for the courtesy shown to applicant's representative during today's telephone interview. The present amendment is made pursuant to that interview.

**Objections to confusing language in claims**

The Examiner has objected to claims 1 to 4 as being in confusing language due to use of the term "quartz glass jig" to refer to both the end product of the process and the intermediate product being processed.

As discussed during the interview, all claims have been amended to recite annealing "a product of the desired shape" so as to remove stress therein, and performing a cleaning treatment on "the product", which is believed to satisfy the Examiner's objection.

**Rejections based on prior art**

Independent Claims 1 to 4 and their dependent claims 5-8, 12-15, 17-20, and 22-25 have been rejected under 35 U.S.C. 103(a) as being unpatentable over Applicant's admitted prior art from the specification, in view of U.S. Pat. No. 6,077,451 to Takenaka et al. (hereinafter referred to as "Takenaka") and further in view of Japanese Patent No. 7,183,240 to Honma et al. (hereinafter referred to as "Honma").

The claims as now formulated clearly define methods that are not suggested by any permissible combination of the references.

As set out during the telephone interview, the urged combination of the Takenaka U.S. patent with the Honma published Japanese application is not proper.

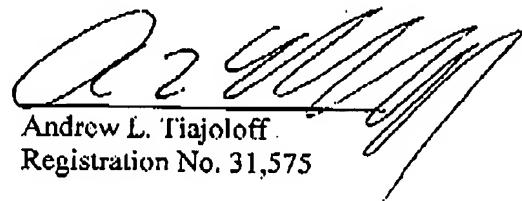
The Honma publication shows gas purification of disassembled parts of a quartz glass jig that are later assembled. See Honma paragraph 11. Honma nowhere suggests or mentions gas etching of the quartz glass jig or its components.

Takenaka teaches a method of assaying a silicon material, which may be quartz glass. In Takenaka a sample has a surface portion etched away, so as to leave a residue on the remaining material. See Takenaka, col. 3, lines 38 to 42. The residue is removed by a solution that dissolves the residue and is then analyzed. See Takenaka, col. 5, lines 20 to 26. Takenaka is silent as to the condition of what is left of the sample M, and in no way suggests any gas purification of the sample M, since Takenaka is not a method directed at purifying the sample.

Therefore, one of skill in the art would not look to the essentially unrelated method of Takenaka when seeking to improve a method of making a quartz glass jig with a cleaner outer surface, such as the method of Honma. It is therefore respectfully submitted that the combination of these references is not appropriate, and reconsideration of the rejection is respectfully requested.

Should any questions arise, the Examiner is invited to telephone attorney for applicants at 212-490-3285.

Respectfully submitted,



Andrew L. Tiajoloff  
Registration No. 31,575

Tiajoloff & Kelly  
Chrysler Building, 37<sup>th</sup> floor  
405 Lexington Avenue  
New York, NY 10174

tel. 212-490-3285  
fax 212-490-3295